

SPECIFICATION AMENDMENTS

Please replace paragraph 0028 with the following rewritten paragraph:

[0028] The measured change in temperature (ΔT) of the bake plate is compared to a temperature change threshold value for a specified time period to determine whether the wafer is properly positioned on the bake plate. Preferably, the temperature change threshold value is 1% of the set point temperature over a time interval of 10 seconds. Normal positioning of the wafer on the bake plate is expressed by the following algorithm: $\Delta T \geq$ Temperature set point $[[* 1\%]] \times .01$ during 10 seconds after transfer of the wafer onto the bake plate. Accordingly, if the temperature of the bake plate rises by at least one percent of the set point temperature during the first ten seconds after transfer of the wafer onto the bake plate, then the wafer is properly positioned for the bake process.

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Please replace paragraph 0028 with the following rewritten paragraph:

[0029] Abnormal positioning of the wafer on the bake plate is expressed by the following algorithm: $\Delta T < \text{Temperature set point} \times .01$ during 10 seconds after transfer of the wafer onto the bake plate. Accordingly, if the temperature of the bake plate fails to rise by at least one percent of the set point temperature during the first ten seconds after transfer of the wafer onto the bake plate, this indicates that the wafer is improperly positioned on the bake plate to begin the bake process. The bake process is then aborted and corrective measures are taken to ensure proper positioning of subsequent wafers on the bake plate.